

INFLUENCE OF DIFFERENT DIGITAL POWER SUPPLY LAYOUT STYLES ON THE EME OF ICS WITH RESPECT TO PROCESS VARIATIONS

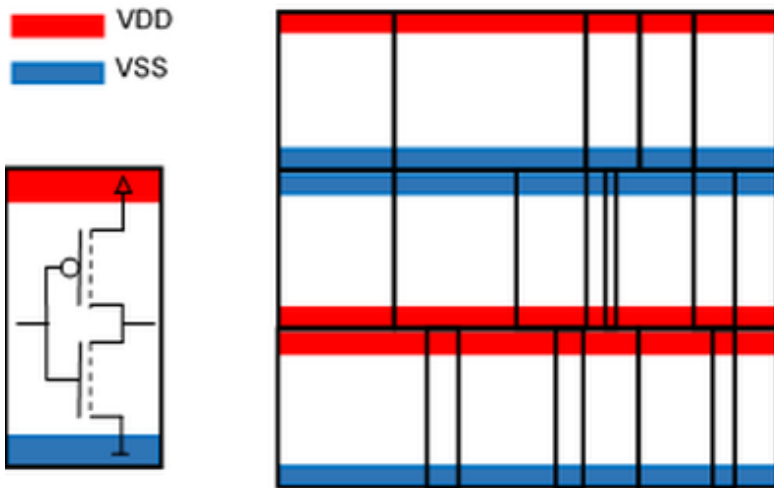


Andreas Rauchenecker and Timm Ostermann
Dept. Energy Efficient Analog Circuits and Systems
Institute for Integrated Circuits
JKU University of Linz/Austria

OVERVIEW

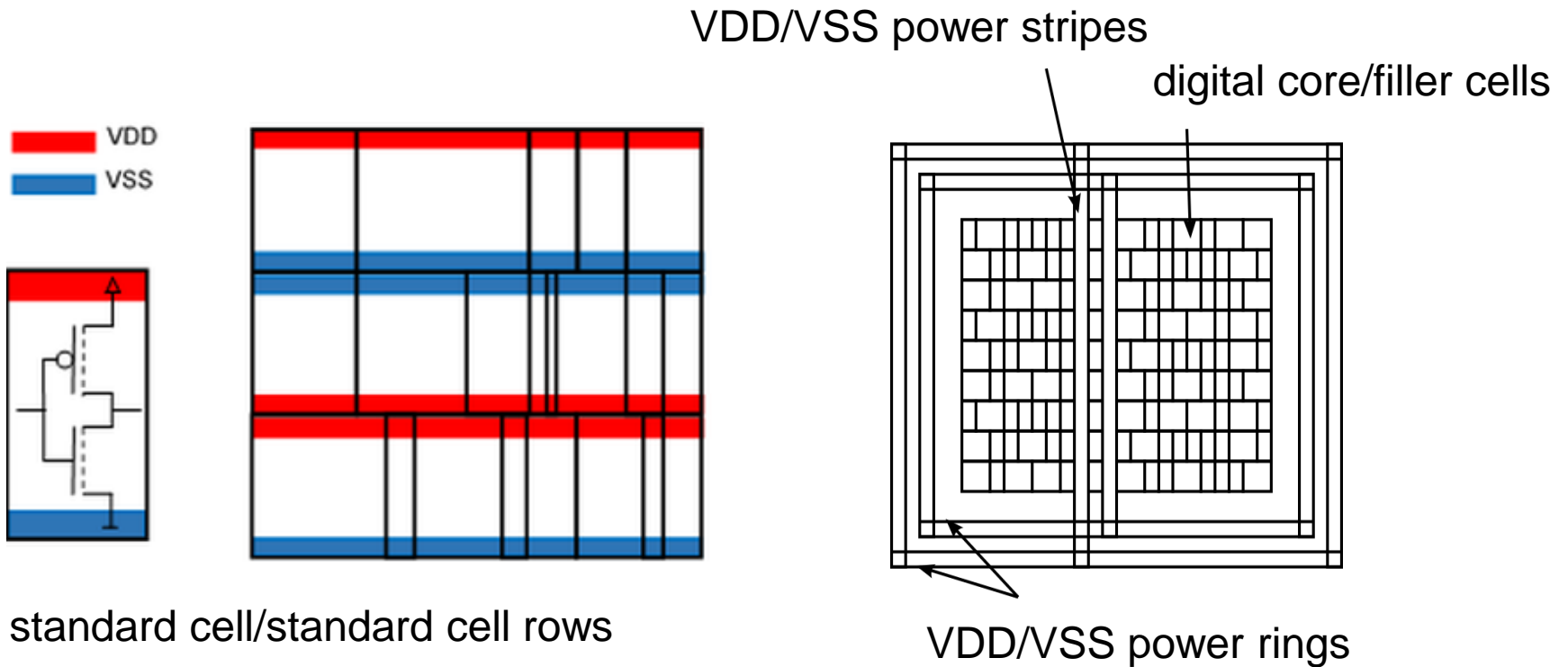
- Standard digital layout
- Test chip
- Process variations
- Measurement
- Conclusion

STANDARD DIGITAL LAYOUT

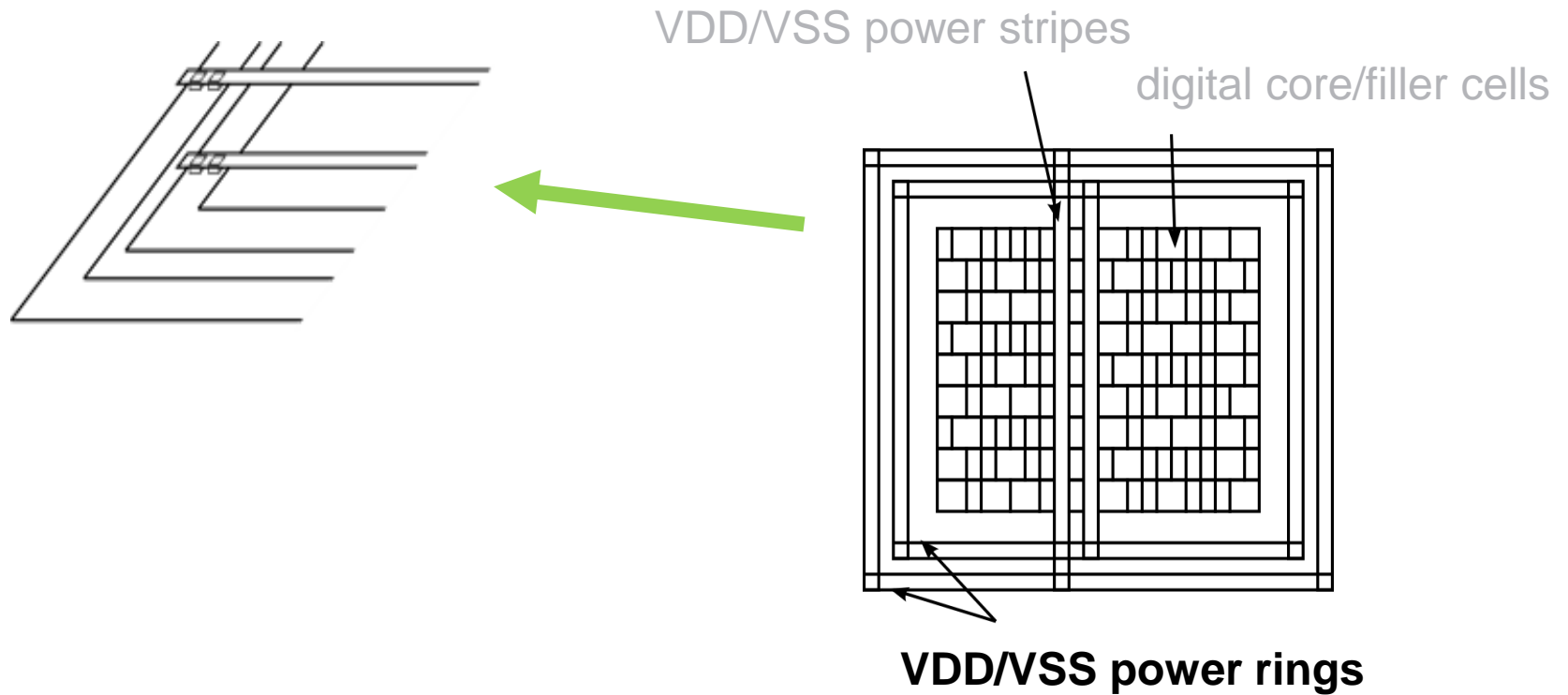


Standard cell/standard cell rows

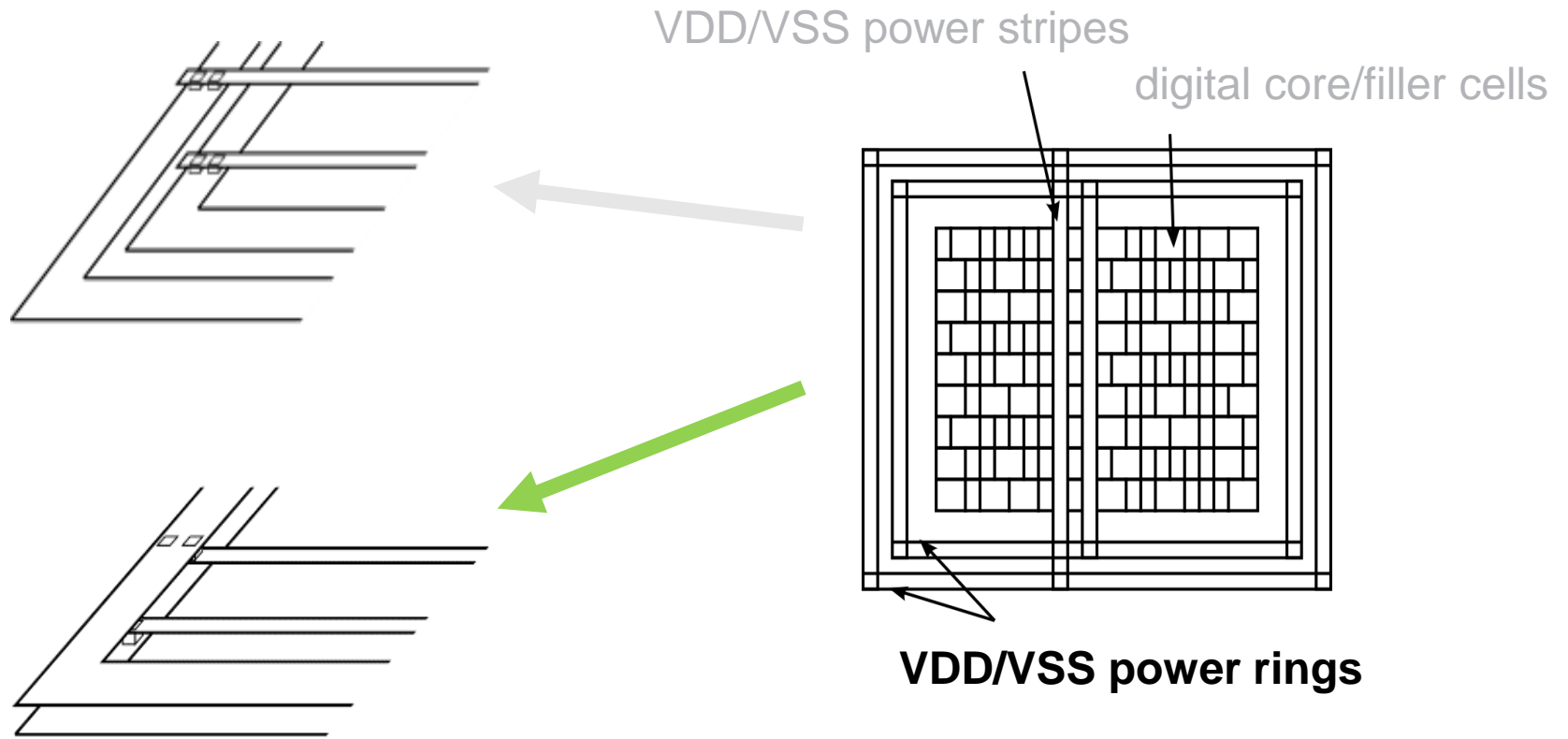
STANDARD DIGITAL LAYOUT



STANDARD DIGITAL LAYOUT

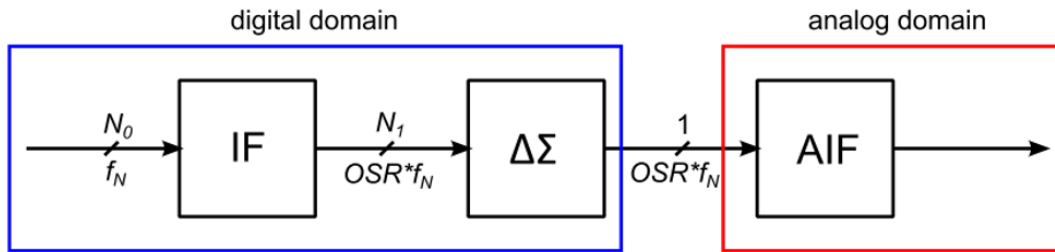


STANDARD DIGITAL LAYOUT



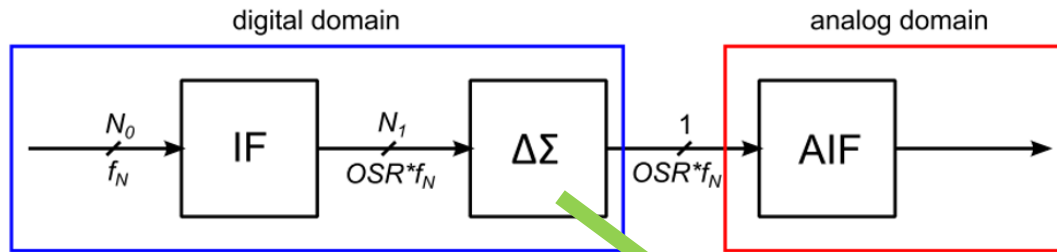
TEST CHIP

Delta sigma digital-to-analog converter ($\Delta\Sigma$ -DAC)



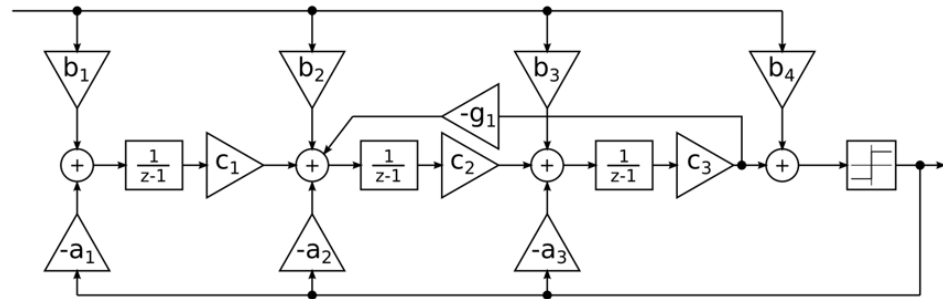
TEST CHIP

Delta sigma digital-to-analog converter ($\Delta\Sigma$ -DAC)



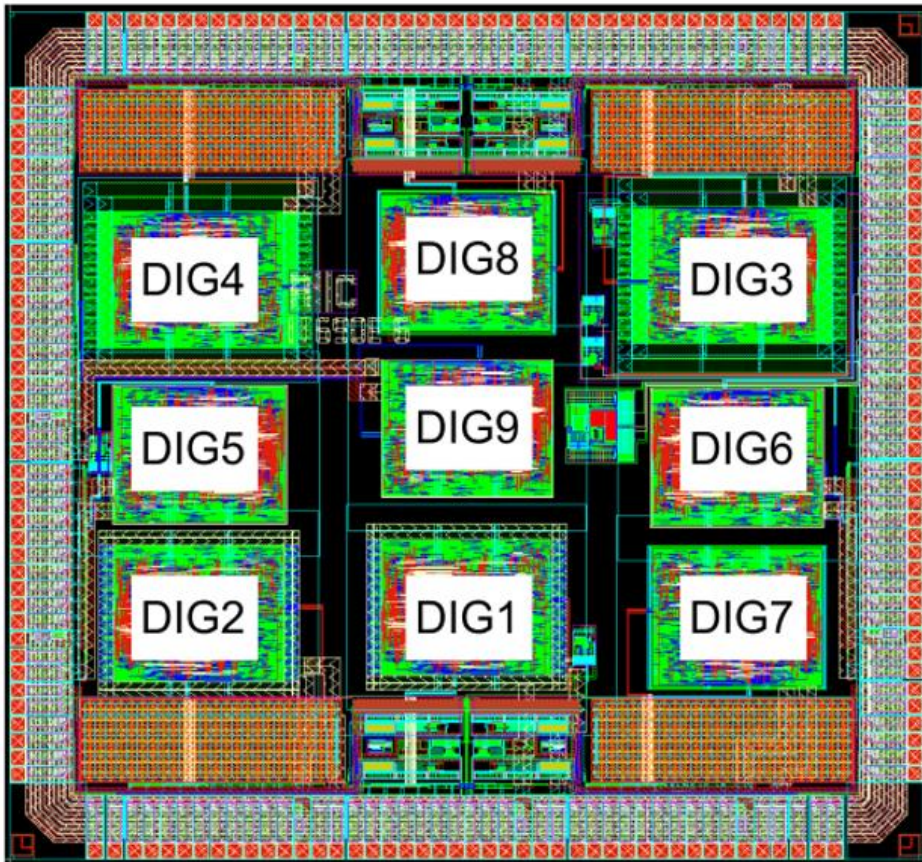
$\Delta\Sigma$ -modulator is realized as a 3rd order CIFB structure

CIFB \rightarrow cascade-of-integrators feedback



TEST CHIP

Top layout

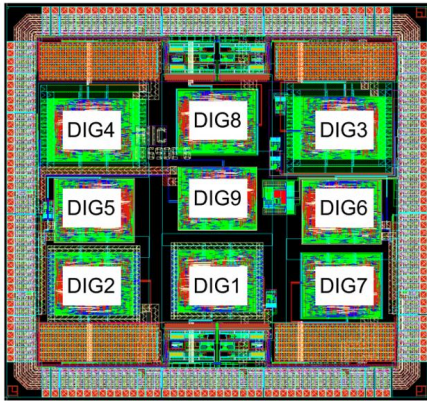


250nm CMOS technology

approx. 32mm²

TEST CHIP

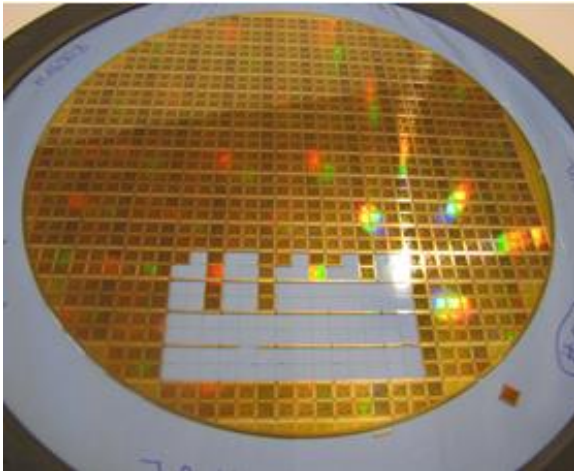
Top layout



Core	Layout Differences			
	<i>Power Ring</i>		<i>Filler Cells Capacitance</i>	<i>Power Stripes</i>
	<i>Width (VDD or VSS)</i>	<i>Arrangement</i>		
DIG1	84 μ m	stacked	with	yes
DIG2	84 μ m	stacked	without	yes
DIG3	84 μ m	flattened	with	yes
DIG4	84 μ m	flattened	without	yes
DIG5	8.4 μ m	stacked	with	yes
DIG6	8.4 μ m	stacked	without	yes
DIG7	8.4 μ m	flattened	with	yes
DIG8	8.4 μ m	flattened	without	no
DIG9	2.1 μ m	stacked	with	yes

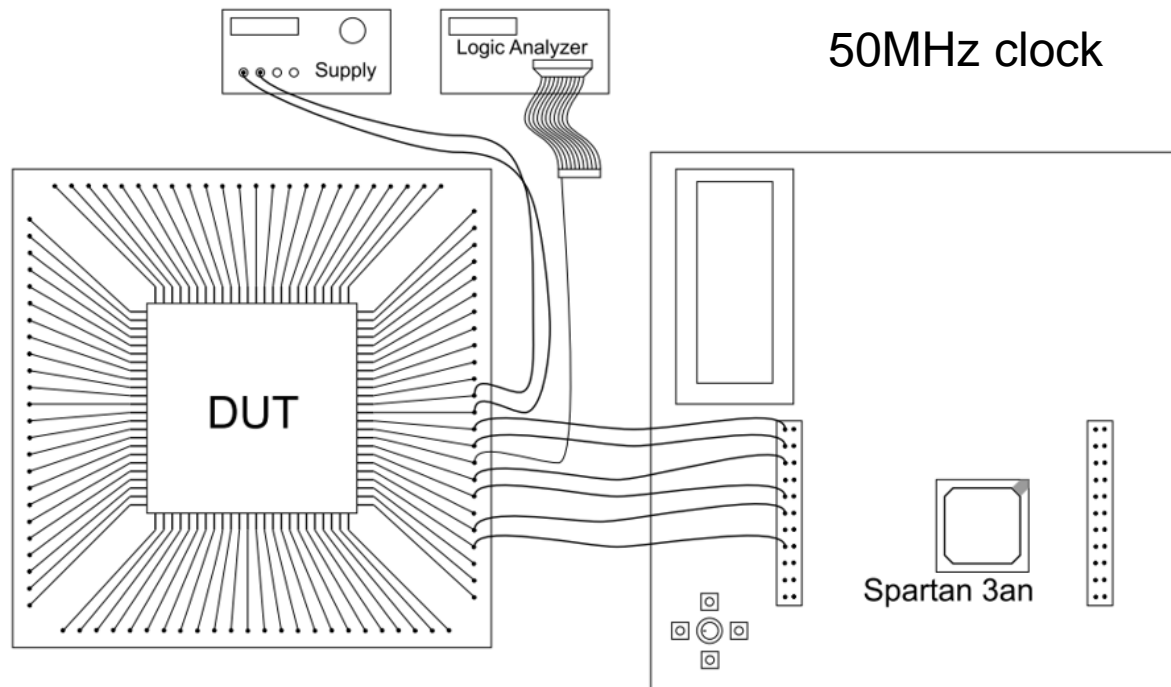
PROCESS VARIATIONS

Split-Lot with 9 different splits (2 wafers each split)

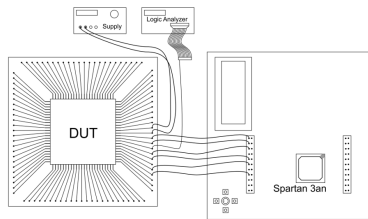


- "NOM" → nominal case
- "FAST" → MOSFETs in fast process corner
- "SLOW" → MOSFETs in slow process corner
- "SF" → nMOSFETs slow / pMOSFETs fast
- "FS" → nMOSFETs fast / pMOSFETs slow
- "HRES" → n-R max., p-R min. values
- "LRES" → n-R min., p-R max. values
- "LGL" → max. gate length values
- "SGL" → min. gate length values

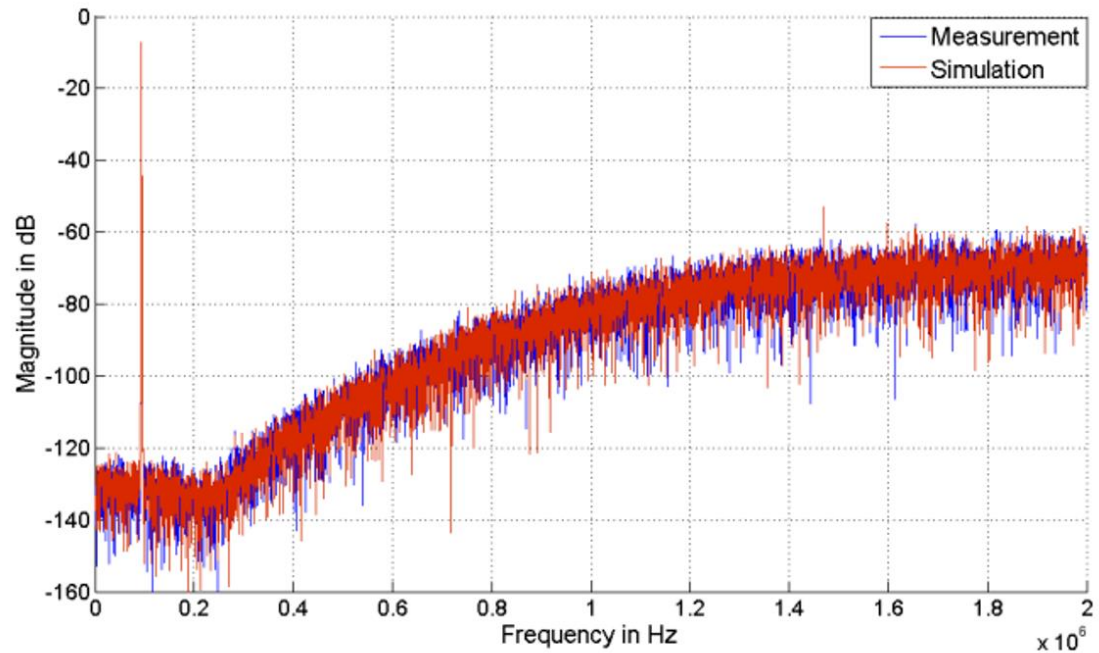
MEASUREMENT → TEST CHIP FUNCTIONALITY



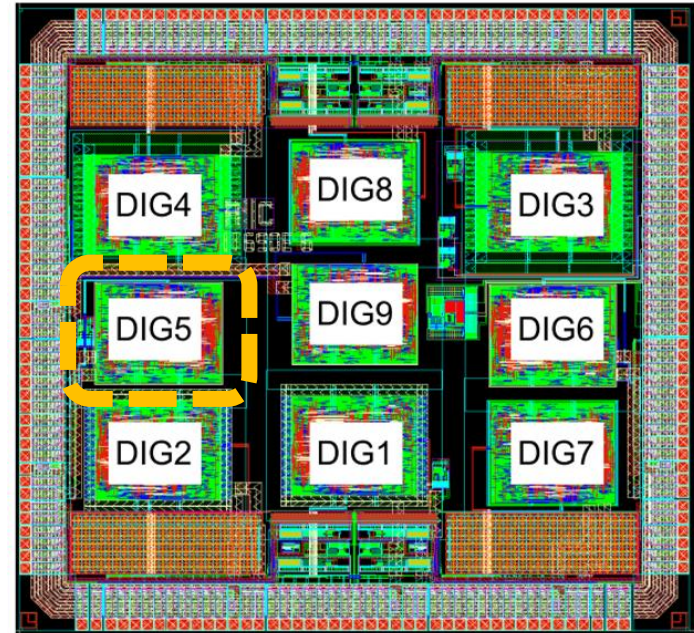
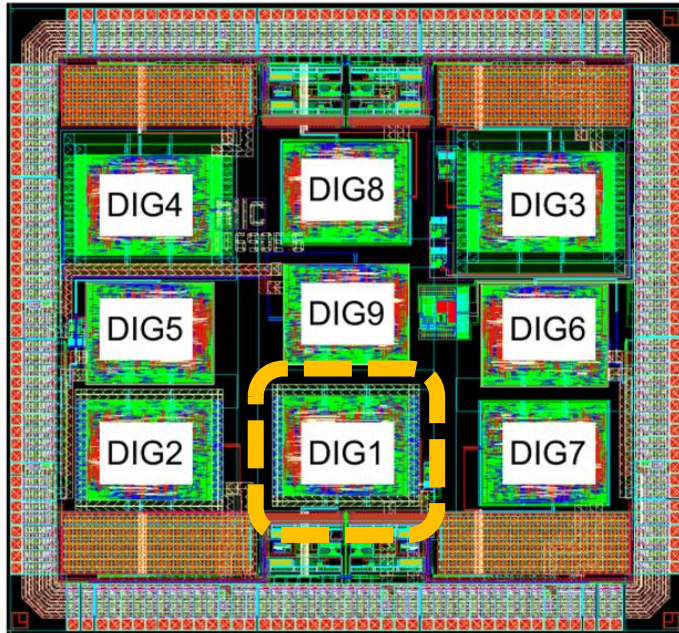
MEASUREMENT → TEST CHIP FUNCTIONALITY



FFT of digital output bitstream



MEASUREMENT



Victim → $\Delta\Sigma$ -DAC1 @ 50MHz

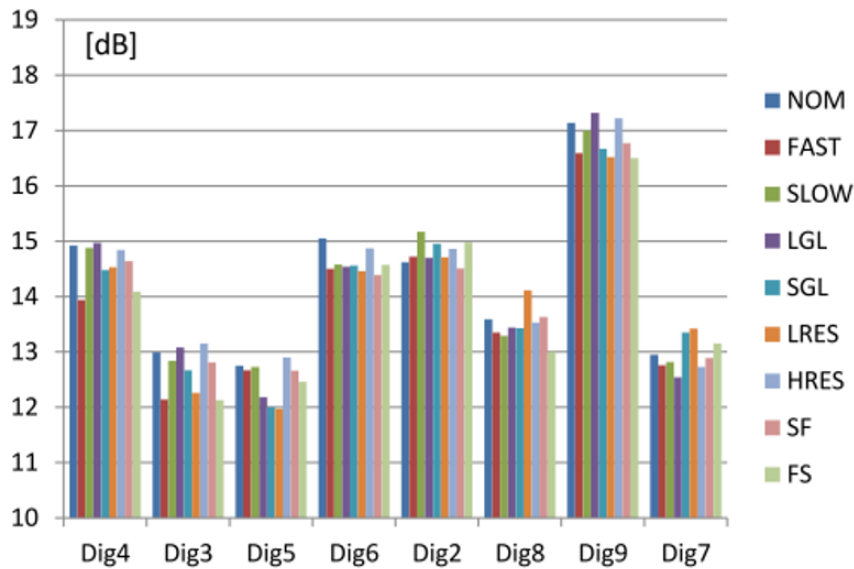
Victim → $\Delta\Sigma$ -DAC5 @ 50MHz

Criteria → parasitic coupling of digital signals into analog output signal
→ Spectrum analyzer @ analog AIF output

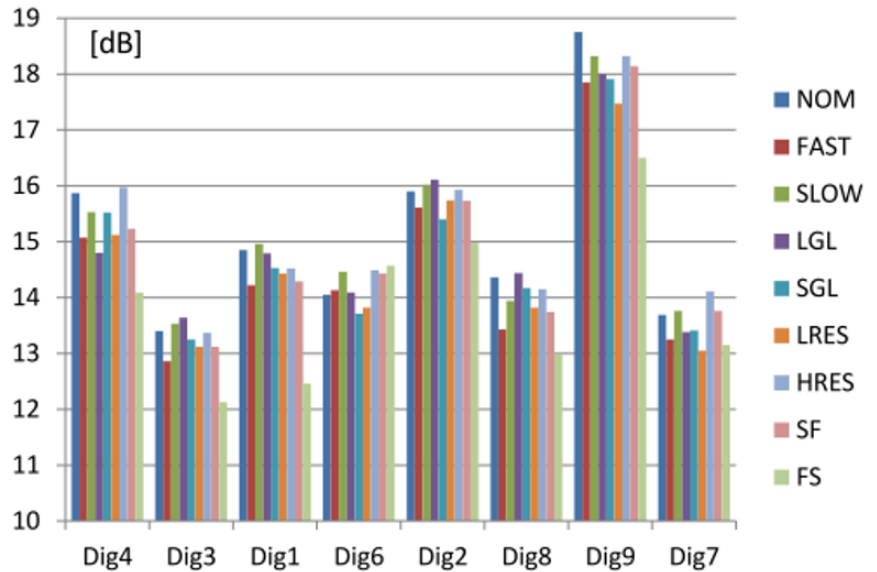
Aggressor → 1 of the other DIG circuits @ 49.5 & 50.5 MHz clock

MEASUREMENT

Difference between 50 MHz coupling and interference at 49.5 MHz



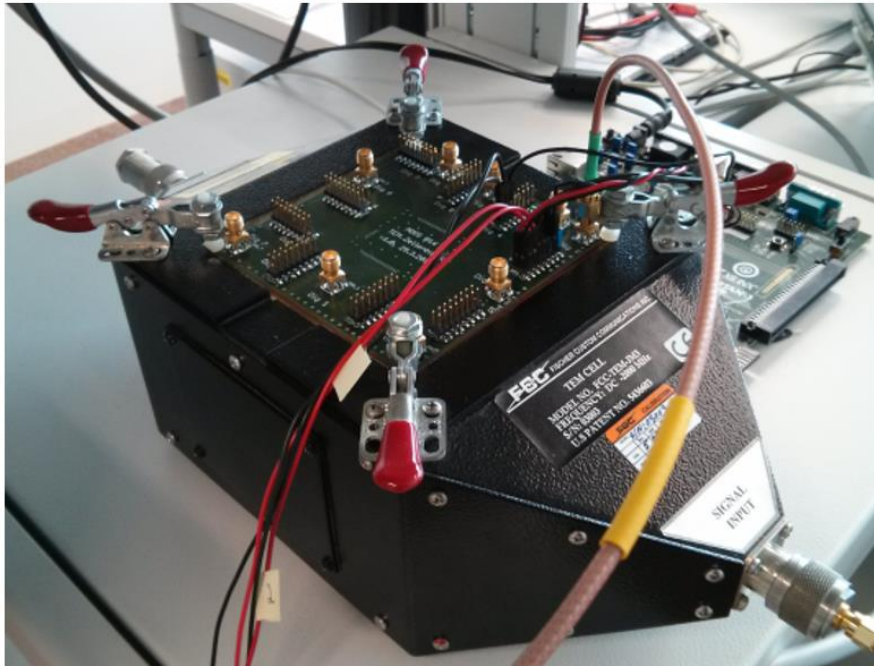
AIF output $\Delta\Sigma$ -DAC1



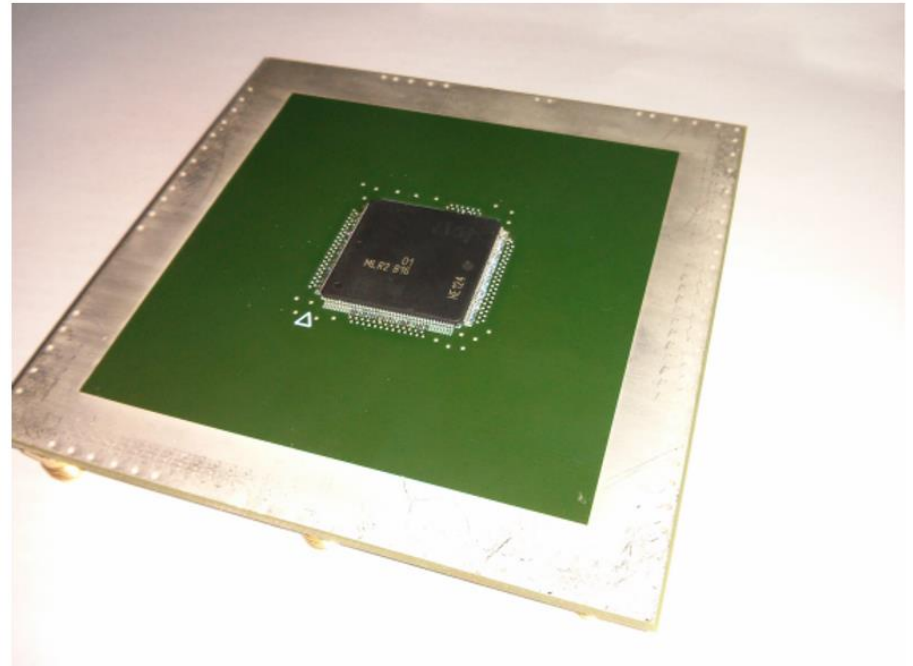
AIF output $\Delta\Sigma$ -DAC5

MEASUREMENT

→ IEC 61967 TEM CELL EME MEASUREMENT



TEM cell with mounted test board

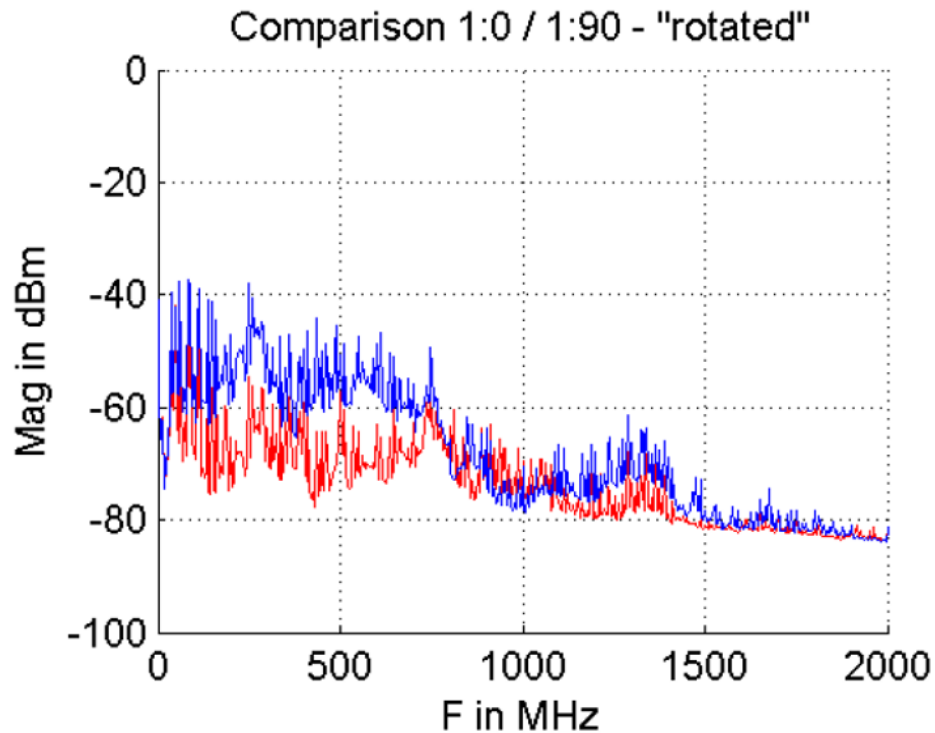


test board with DUT

- 1 50Ω TEM cell port is terminated with 50Ω load
- 1 50Ω TEM-cell port is connected to the input of a spectrum analyzer
- DUT is measured four times, each time rotated by 90°

MEASUREMENT

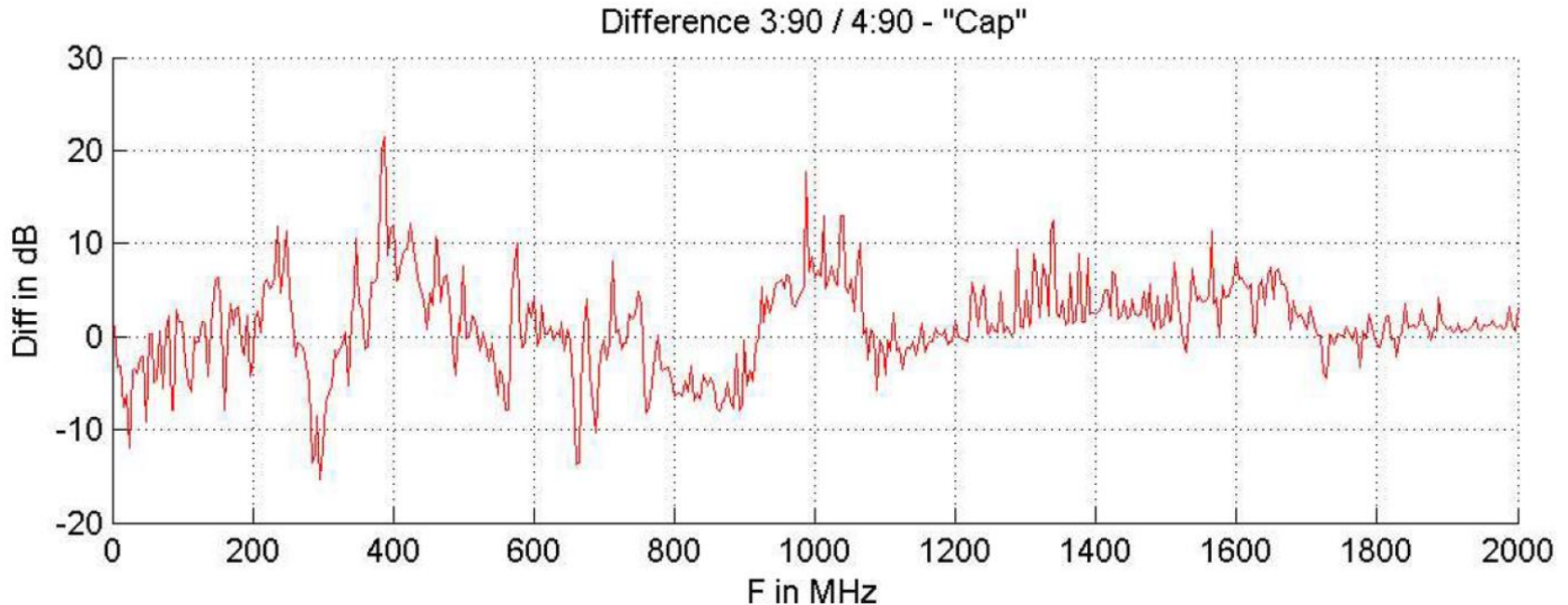
→ IEC 61967 TEM CELL EME MEASUREMENT



Measurement of $\Delta\Sigma$ -DAC1 (nominal corner)
@ 50MHz, [9 kHz - 2 GHz]

MEASUREMENT

→ IEC 61967 TEM CELL EME MEASUREMENT



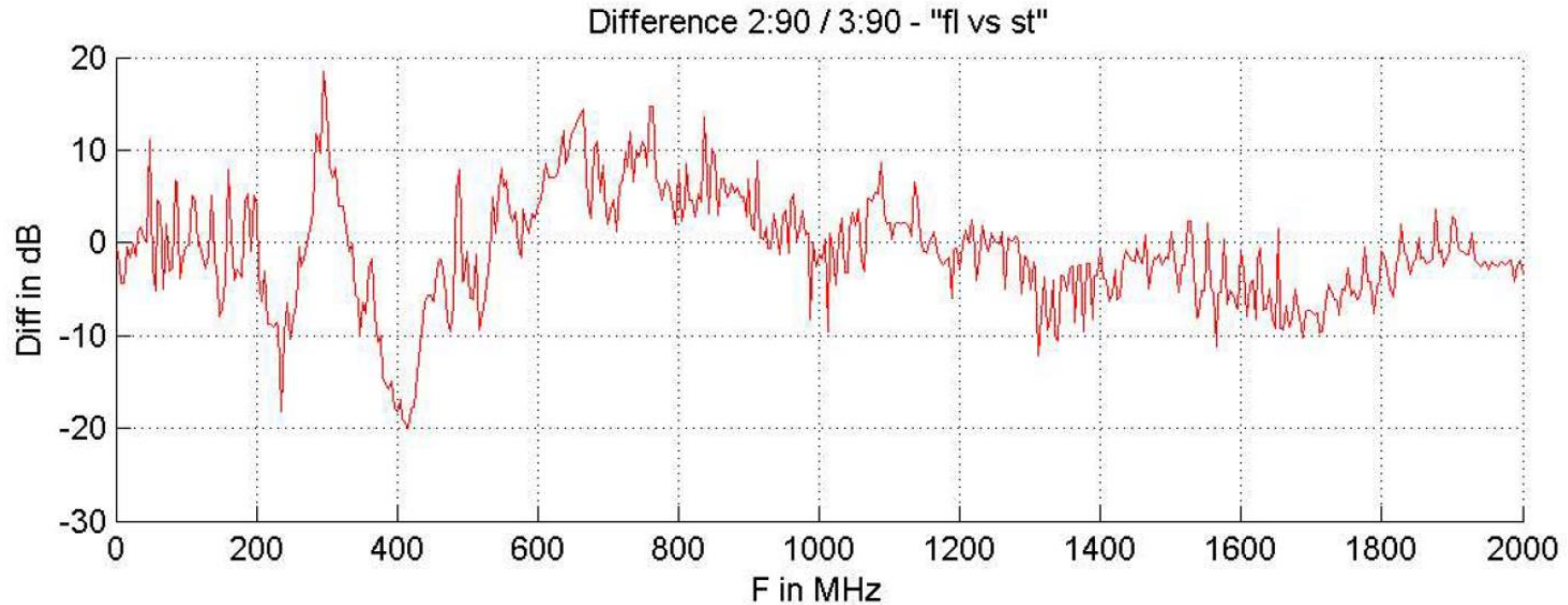
Differences between the measured EME of

→ DIG3 (filler cells with capacitances)

→ DIG4 (filler cells without capacitances)

MEASUREMENT

→ IEC 61967 TEM CELL EME MEASUREMENT



Influence of the power ring layout between DIG2 (stacked) and DIG3 (flattened)

Again no improvement over the whole frequency range can be observed for neither variant.

CONCLUSION

■ Overall recommendation:

- Stacking the power rings to save space can be recommended, at least as long as no routing problems occur.
- Stacking of the power rings result in no degradation considering emissions.
- Considering emissions only, the use of filler cells with capacitances has no benefits. Although their use can be recommended as they reduce on chip interferences.

THANK YOU!

